## Adhesion and Friction in Polymer Films on Solid Substrates: Conformal Sites Analysis and Corresponding Surface Measurements

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**Fig. S1** Schematic diagram showing the basic operating principle of Nano-TA and a representative deflection curve for a PS film (thickness = 340 nm) on a silica surface.



Fig. S2 Polymer structures and bead center locations chosen for  $poly(\alpha$ -methylstyrene) (PAMS).

Table S1.	Site mole fr	actions and	potential e	energy param	eters <sup>1</sup> for PA	MS with	<i>M<sub>w</sub></i> =450 k	Da
(OPLS for	ce field)							

PAMS	$\varepsilon_{v}/k_{\mathrm{B}}(\mathrm{K})$	X <sub>v</sub>	$\sigma_{ m v}$ (nm)
CH <sub>3</sub> (sp <sup>3</sup> ) <sup>2</sup>	88.1	0.0004	0.390
CH <sub>2</sub> (sp <sup>3</sup> ) <sup>2</sup>	59.4	0.071	0.390
C (aliphatic) <sup>3</sup>	33.2	0.071	0.350
C (aromatic) <sup>3</sup>	35.2	0.071	0.355
H (aromatic) <sup>3</sup>	17.4	0.357	0.242
C (aromatic link) <sup>3</sup>	38.3	0.357	0.355

ΡΜΜΑ	$arepsilon_{ u}/k_{ m B}$ (K)	Χ <sub>ν</sub>	$\sigma_{v}$ (nm)
CH <sub>3</sub> (sp <sup>3</sup> ) <sup>2</sup>	88.1	0.143	0.390
CH <sub>2</sub> (sp <sup>3</sup> ) <sup>2</sup>	59.4	0.143	0.390
C (sp <sup>3</sup> ) <sup>3</sup>	33.2	0.143	0.350
C (carbonyl) <sup>3</sup>	52.8	0.143	0.375
O (carbonyl) <sup>3</sup>	106	0.143	0.296
O (ether) <sup>6</sup>	85.6	0.143	0.300
CH₃ (ether)²	85.6	0.143	0.380

Table S2. Site mole fractions and potential energy parameters<sup>4, 5</sup> for PMMA with  $M_w \approx 100$  kDa (OPLS force field)

Table S3. The structural parameters of Au<sup>7, 8</sup> and silica surfaces,<sup>9</sup> and parameters for the reference system to calculate wetting parameters for PMMA-Au and PAMS-silica systems

		silica	Au
	$ ho_s$ (nm <sup>-3</sup> )	44.2	0.59
	Δ <sub>s</sub> (nm)	0.220	0.288
	$\sigma_{ss}$ (nm)	0.270	0.257
	$\varepsilon_{ss}/k_{ m B}$ (K)	230	5310
ΡΝΛΙΜΔ	$\varepsilon_{xs}/k_{\rm B}$ (K)	/	607
	$\sigma_{xs}$ (nm)	/	0.308

	$\varepsilon_x/k_{\rm B}({\rm K})$		69.6	
	$\sigma_x$ (nm)		0.356	
	α <sub>wx</sub>	/		0.141
	$\varepsilon_{xs}/k_{\rm B}$ (K)	86.3		/
	$\sigma_{xs}$ (nm)	0.287		/
PAMS	$\varepsilon_x/k_{\rm B}$ (K)		32.1	
	$\sigma_x$ (nm)		0.304	
	α <sub>wx</sub>	0.051		/

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